

L Number	Hits	Search Text	DB	Time stamp
1	1038	((thermal\$2 adj2 (oxidation or oxidizing or oxidized)) adj3 (cvd or (chemical adj vapor adj deposition) adj2 chamber) and (@ad<20011012 or @rlad<20011012))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/05/26 11:13
2	101	((("no".u/c. or (nitric with oxide)) same temperature same pressure same (cvd or (chemical adj vapor adj deposition))) and (@ad<20011012 or @rlad<20011012))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/05/26 11:22
3	0	((thermal\$2 adj2 (oxidation or oxidizing or oxidized)) adj3 (cvd or (chemical adj vapor adj deposition) adj2 chamber) and (@ad<20011012 or @rlad<20011012)) and (((("no".u/c. or (nitric with oxide)) same temperature same pressure same (cvd or (chemical adj vapor adj deposition))) and (@ad<20011012 or @rlad<20011012))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/05/26 11:14
4	0	((thermal\$2 adj (oxidation or oxidizing or oxidized) adj in adj2 (cvd or (chemical adj vapor adj deposition)) adj chamber) and (@ad<20011012 or @rlad<20011012))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/05/26 11:15
5	28	((thermal\$2 with (oxidation or oxidizing or oxidized) with (cvd or (chemical adj vapor adj deposition) with chamber with in) and (@ad<20011012 or @rlad<20011012))) and (((("no".u/c. or (nitric with oxide)) with (cvd or (chemical adj vapor adj deposition))) and (@ad<20011012 or @rlad<20011012))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/05/26 11:18
6	19	form\$3 with thermal\$3 with oxide with in with cvd with (furnace or chamber)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/05/26 11:22
7	0	((("no".u/c. or (nitric with oxide)) same temperature same pressure same (cvd or (chemical adj vapor adj deposition))) and (@ad<20011012 or @rlad<20011012)) and (form\$3 with thermal\$3 with oxide with in with cvd with (furnace or chamber))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/05/26 11:22
8	17	(form\$3 with thermal\$3 with oxide with in with cvd with (furnace or chamber)) and ("no".u/c. or (nitric with oxide))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/05/26 11:22
-	355	(gate with oxide) and (oxidiz\$3 with substrate) and (nitrid\$5 with (no or (nitric with oxide))) and cvd	USPAT; EPO; JPO; DERWENT	2004/01/08 15:52
-	197	((gate with oxide) and (oxidiz\$3 with substrate) and (nitrid\$5 with (no or (nitric with oxide))) and cvd) and temperature and (atm or atmosphere or torr)	USPAT; EPO; JPO; DERWENT	2002/07/30 14:02
-	149	((gate with oxide) and (oxidiz\$3 with substrate) and (nitrid\$5 with (no or (nitric with oxide))) and cvd) and temperature and (atm or atmosphere or torr) and 438/\$3.ccls.	USPAT; EPO; JPO; DERWENT	2002/07/30 14:02
-	119	((gate with oxide) and (oxidiz\$3 with substrate) and (nitrid\$5 with (no or (nitric with oxide))) and cvd) and temperature and (atm or atmosphere or torr) and 438/\$3.ccls.) and (gate with electrode)	USPAT; EPO; JPO; DERWENT	2002/07/30 13:55
-	145	(gate with oxide) same (oxidiz\$3 with substrate) and (nitrid\$5 with (no or (nitric with oxide))) and cvd	USPAT; EPO; JPO; DERWENT	2002/07/31 15:55
-	76	((gate with oxide) same (oxidiz\$3 with substrate) and (nitrid\$5 with (no or (nitric with oxide))) and cvd) and temperature and (atm or atmosphere or torr)	USPAT; EPO; JPO; DERWENT	2002/07/30 14:02

-	59	((gate with oxide) same (oxidiz\$3 with substrate) and (nitrid\$5 with (no or (nitric with oxide))) and cvd) and temperature and (atm or atmosphere or torr)) and 438/\$3.ccls.	USPAT; EPO; JPO; DERWENT	2002/07/30 14:02
-	5	(gate with oxide) same (oxidiz\$3 with substrate) and ((nitrid\$5 with (no or (nitric with oxide))) same boron)) and cvd	USPAT; EPO; JPO; DERWENT	2002/07/30 15:11
-	17	"5650344"	USPAT; EPO; JPO; DERWENT	2002/07/30 15:11
-	14	"5403786"	USPAT; EPO; JPO; DERWENT	2002/07/31 14:16
-	26	(gate with oxide) same (oxidiz\$3 with substrate) and (nitrid\$5 with (no or (nitric with oxide))) and cvd and ono and (gate adj electrode)	USPAT; EPO; JPO; DERWENT	2002/07/31 15:57
-	22	(gate with oxide) same (oxidiz\$3 with substrate) and (nitrid\$5 with (no or (nitric with oxide))) and cvd and ono and ((gate adj electrode) with (silicon or polysilicon))	USPAT; EPO; JPO; DERWENT	2002/07/31 16:33
-	11	((gate with oxide) same (oxidiz\$3 with substrate) and (nitrid\$5 with (no or (nitric with oxide))) and cvd and ono and ((gate adj electrode) with (silicon or polysilicon))) and tungsten	USPAT; EPO; JPO; DERWENT	2002/07/31 15:58
-	3	(gate with oxide) same (oxidiz\$3 with substrate) and (nitrid\$5 with (no or (nitric with oxide))) and cvd and ono and (((gate adj electrode) with polycide) same tungsten)	USPAT; EPO; JPO; DERWENT	2002/07/31 16:56
-	17	"5650344"	USPAT; EPO; JPO; DERWENT	2002/07/31 16:56
-	3554	(nitrid\$5 with gate with oxide) and cvd	USPAT; EPO; JPO; DERWENT	2003/01/13 12:32
-	0	((nitrid\$5 with gate with oxide) same (nitirc adj oxide)) and cvd	USPAT; EPO; JPO; DERWENT	2003/01/13 12:33
-	5	((nitrid\$5 with gate with oxide) same (nitric adj oxide)) and cvd	USPAT; EPO; JPO; DERWENT	2003/01/13 12:33
-	6	((nitrid\$5 with gate with oxide) same (nitric adj oxide)) and cvd	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/01/13 14:55
-	0	11040681.URPN.	USPAT	2003/01/13 14:46
-	2	5726087.pn.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/01/13 16:28
-	355	dry adj oxide	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/01/13 16:49
-	518	(gate adj oxide) with angstrom with ("10" or "15" or "20")	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/01/13 16:51
-	341	(gate adj oxide) with angstrom with ("10" or "15")	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/01/13 17:23
-	234	((gate adj oxide) with angstrom with ("10" or "15")) and nitrid\$5	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/01/13 17:06

-	46	((gate adj oxide) with angstrom with ("10" or "15")) same nitrid\$5	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/01/13 17:06
-	8	(gate adj oxide) with angstrom with ("10" or "15") with (ultra near2 thin)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/01/13 17:24
-	121	(no or (nitric with oxide)) and cvd and (nitrogen with dop\$3 with oxide) and (thermal adj oxidation)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/08 15:58
-	108	((no or (nitric with oxide)) and cvd and (nitrogen with dop\$3 with oxide) and (thermal adj oxidation)) and (@ad<20011012 or @rlad<20011012)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/08 15:59
-	100	("no".u/c. or (nitric with oxide)) and cvd and (nitrogen with dop\$3 with oxide) and (thermal adj oxidation)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/08 18:14
-	93	((("no".u/c. or (nitric with oxide)) and cvd and (nitrogen with dop\$3 with oxide) and (thermal adj oxidation)) and (@ad<20011012 or @rlad<20011012)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/08 18:15
-	88	("no".u/c. or (nitric with oxide)) and cvd and ((thermal adj oxidation) same (thermal adj nitridation))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/08 18:15
-	85	((("no".u/c. or (nitric with oxide)) and cvd and ((thermal adj oxidation) same (thermal adj nitridation))) and (@ad<20011012 or @rlad<20011012)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/08 18:32
-	2	("no".u/c. or (nitric with oxide)) and cvd and ((thermal adj oxidation) same (thermal adj nitridation) same (gate adj oxide))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/08 18:32
-	31	("no".u/c. or (nitric with oxide)) and cvd and ((thermal adj oxidation) same (gate adj oxide)) and (thermal adj nitridation)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/08 18:32
-	30	((("no".u/c. or (nitric with oxide)) and cvd and ((thermal adj oxidation) same (gate adj oxide)) and (thermal adj nitridation)) and (@ad<20011012 or @rlad<20011012)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/05/19 16:27
-	580	("no".u/c. or (nitric with oxide)) and cvd and (thermal\$2 with oxidation) and (nitriding or nitridation) and temperature and pressure and (@ad<20011012 or @rlad<20011012)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/05/19 16:30
-	16	((("no".u/c. or (nitric with oxide)) same (nitriding or nitridation) same temperature and pressure) and (thermal\$2 same (oxidation or oxidizing or oxidized) same temperature same pressure) and cvd and (@ad<20011012 or @rlad<20011012)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/05/19 17:00
-	246	(thermal\$2 with (oxidation or oxidizing or oxidized) with (cvd or (chemical adj vapor adj deposition)) same temperature same pressure) and (@ad<20011012 or @rlad<20011012)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/05/19 16:59
-	10	((("no".u/c. or (nitric with oxide)) same (nitriding or nitridation) same temperature same pressure same (cvd or (chemical adj vapor adj deposition))) and (@ad<20011012 or @rlad<20011012)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/05/19 17:04

-	1	((thermal\$2 with (oxidation or oxidizing or oxidized) with (cvd or (chemical adj vapor adj deposition)) same temperature same pressure) and (@ad<20011012 or @rlad<20011012)) and (((no".u/c. or (nitric with oxide)) same (nitriding or nitridation) same temperature same pressure same (cvd or (chemical adj vapor adj deposition))) and (@ad<20011012 or @rlad<20011012))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/05/25 18:24
-	101	((("no".u/c. or (nitric with oxide)) same temperature same pressure same (cvd or (chemical adj vapor adj deposition))) and (@ad<20011012 or @rlad<20011012))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/05/26 11:14
-	8	((thermal\$2 with (oxidation or oxidizing or oxidized) with (cvd or (chemical adj vapor adj deposition)) same temperature same pressure) and (@ad<20011012 or @rlad<20011012)) and (((no".u/c. or (nitric with oxide)) same temperature same pressure same (cvd or (chemical adj vapor adj deposition))) and (@ad<20011012 or @rlad<20011012))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/05/19 17:04
-	19	((("no".u/c. or (nitric with oxide)) same temperature same (gate with (oxide or dielectric)) same pressure same (cvd or (chemical adj vapor adj deposition))) and (@ad<20011012 or @rlad<20011012))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/05/20 07:19
-	6	((("no".u/c. or (nitric with oxide)) with (cvd or (chemical adj vapor adj deposition)) with in with (nitriding or nitridation)) and (@ad<20011012 or @rlad<20011012))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/05/20 07:29
-	30	((("no".u/c. or (nitric with oxide)) with (cvd or (chemical adj vapor adj deposition)) with in) and (@ad<20011012 or @rlad<20011012))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/05/20 07:49
-	0	((("no".u/c. or (nitric with oxide)) with (cvd or (chemical adj vapor adj deposition)) with in with (nitriding or nitridation)) and (@ad<20011012 or @rlad<20011012)) not (((no".u/c. or (nitric with oxide)) with (cvd or (chemical adj vapor adj deposition)) with in) and (@ad<20011012 or @rlad<20011012))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/05/20 07:29
-	24	((("no".u/c. or (nitric with oxide)) with (cvd or (chemical adj vapor adj deposition)) with in) and (@ad<20011012 or @rlad<20011012)) not (((no".u/c. or (nitric with oxide)) with (cvd or (chemical adj vapor adj deposition)) with in with (nitriding or nitridation)) and (@ad<20011012 or @rlad<20011012))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/05/20 07:30
-	6	((("no".u/c. or (nitric with oxide)) with (cvd or (chemical adj vapor adj deposition)) with furnace) and (@ad<20011012 or @rlad<20011012))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/05/25 18:26
-	4134	(thermal\$2 with (oxidation or oxidizing or oxidized) with (cvd or (chemical adj vapor adj deposition) with chamber with in) and (@ad<20011012 or @rlad<20011012))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/05/25 18:53
-	266	((("no".u/c. or (nitric with oxide)) with (cvd or (chemical adj vapor adj deposition))) and (@ad<20011012 or @rlad<20011012))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/05/25 18:27

-	13	((thermal\$2 with (oxidation or oxidizing or oxidized) with (cvd or (chemical adj vapor adj deposition) with chamber with in) and (@ad<20011012 or @rlad<20011012))) and (((no".u/c. or (nitric with oxide)) with (cvd or (chemical adj vapor adj deposition))) and (@ad<20011012 or @rlad<20011012))) and temperature and pressure	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/05/25 18:27
-	1038	(thermal\$2 adj2 (oxidation or oxidizing or oxidized) adj3 (cvd or (chemical adj vapor adj deposition) adj2 chamber) and (@ad<20011012 or @rlad<20011012))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/05/26 11:13
-	0	(thermal\$2 adj (oxidation or oxidizing or oxidized) adj in adj2 (cvd or (chemical adj vapor adj deposition) adj chamber) and (@ad<20011012 or @rlad<20011012))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/05/25 18:58
-	0	(thermal\$2 adj2 (oxidation or oxidizing or oxidized) adj2 in adj2 (cvd or (chemical adj vapor adj deposition) adj2 chamber) and (@ad<20011012 or @rlad<20011012))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/05/25 18:54
-	0	(thermal\$2 adj3 (oxidation or oxidizing or oxidized) adj3 in adj3 (cvd or (chemical adj vapor adj deposition) adj3 chamber) and (@ad<20011012 or @rlad<20011012))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/05/25 18:58
-	0	(thermal\$2 adj oxidation adj in adj (cvd or (chemical adj vapor adj deposition) adj chamber) and (@ad<20011012 or @rlad<20011012))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/05/25 18:57
-	543	(thermal\$2 adj oxidation adj (cvd or (chemical adj vapor adj deposition) adj chamber) and (@ad<20011012 or @rlad<20011012))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/05/25 18:57
-	0	((thermal\$2 adj (oxidation or oxidizing or oxidized) adj in adj2 (cvd or (chemical adj vapor adj deposition)) adj chamber) and (@ad<20011012 or @rlad<20011012))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/05/26 11:15
-	0	((thermal\$2 adj3 (oxidation or oxidizing or oxidized) adj3 in adj3 (cvd or (chemical adj vapor adj deposition)) adj3 chamber) and (@ad<20011012 or @rlad<20011012))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/05/25 18:59